Presented at the 6<sup>th</sup> Workshop on RF Superconductivity October 4-8, 1993, CEBAF, Newport News, Virginia

# Hydrogen Contamination of Niobium Surfaces V. Nguyen-Tuong and Lawrence R. Doolittle

# INTRODUCTION

The presence of hydrogen is blamed for dramatic reductions in cavity Q's.<sup>1-7</sup> Hydrogen concentration is difficult to measure, so there is a great deal of Fear, Uncertainty, and Doubt (FUD) associated with the problem. This paper presents measurements of hydrogen concentration depth profiles, commenting on the pitfalls of the methods used and exploring how material handling can change the amount of hydrogen in pieces of niobium.

Hydrogen analysis was performed<sup>8</sup> by a forward scattering experiment with Helium used as the primary beam.<sup>9</sup> This technique is variously known as FRES (Forward Recoil Elastic Scattering), FRS, HFS (Hydrogen Forward Scattering), and HRA (Hydrogen Recoil Analysis). Some measurements were also made using SIMS (Secondary Ion Mass Spectrometry).

Both HFS and SIMS are capable of measuring a depth profile of Hydrogen. The primary difficulty in interpreting the results from these techniques is the presence of a surface peak which is due (at least in part) to contamination with either water or hydrocarbons.

With HFS, the depth resolution is about 30 nm, and the maximum depth profiled is about 300 nm. (This 10-1 ratio is unusually low for ion beam techniques, and is a consequence of the compromises that must be made in the geometry of the experiment, surface roughness, and energy straggling in the absorber foil that must be used to filter out the forward scattered helium.)

All the observed HFS spectra include a "surface peak" which includes both surface contamination and any real hydrogen uptake by the niobium surface. Some contamination occurs during the analysis. The vacuum in the analysis chamber is typically a few times  $10^{-6}$  torr, and some of the contamination is in the form of hydrocarbons from the pumping system. Hydrocarbons normally form a very thin (less than a monolayer) film which is in equilibrium between arrival rate and the evaporation rate. In the presence of the incoming ion beam, however, these hydrocarbons crack on the surface into non-volatile components. Equilibrium is lost, and the surface builds up a layer of carbon-based gunk. A key question in this analysis is what depth scale is involved in the environmental contamination. The diffusion constant of dissolved hydrogen (in the  $\alpha$ -Nb phase) at room temperature is quite high, making it unlikely that significant non-uniformities will be observed in that part of the sample. On the other hand, the surface of niobium, after treatment and exposure to air is known to have other phases present, primarily oxides. Hydrogen content in these other phases will be different from that in the  $\alpha$  phase, even under equilibrium conditions. Furthermore, the diffusion coefficient of hydrogen in an oxide phase is lower that that in metals. Finally, hydrogen and stress are known to interact in niobium; this is relevant because the surface layer of mechanically worked (rolled) samples is typically highly stressed.

In some of the discussions below, we will use the concept of "bulk" concentration - this is a codeword for the top 200 nm, not counting surface contamination. This is both the region that is sampled by HFS, and is the relevant region for determining RF properties because the penetration depth for 1.5 GHz RF fields in niobium is about 36 nm.

# EXPERIMENTAL PROCEDURE

The samples, 1 cm  $\times$  1 cm  $\times$  0.15 cm in size, were cut from reactor grade (RRR=40) and high purity (RRR=250) sheets of niobium. Surface roughnesses of about 1  $\mu$ m rms (reactor grade) and 0.14  $\mu$ m rms (high purity) were measured by stylus techniques on the unprocessed samples. The surface treatments applied to the various pieces were selected as being typical for the preparation of superconducting cavities. Table 1 summarizes which samples received which treatments, using the shorthand description elaborated below.

As-received: The samples were degreased, rinsed with DI (deionized) water, and cleaned with reagent grade methanol.

BCP: Chemical polishing is done in a buffered solution of equal parts of hydrofluoric (49%), nitric(70%) and phosphoric (85%) acids. After the polishing operation, the sample is rinsed in DI water and in methanol.

CP: Chemical polishing is done in a solution of 40% hydrofluoric acid (40%), and 60% nitric acid (70%). After the polishing operation, the sample is rinsed in DI water and in methanol.

Anodized 100V: Anodic oxidation is carried out in a diluted ammonium hydroxide solution (10%) at a voltage of 100V. Based on anodization conditions, the thickness of the Nb<sub>2</sub>O<sub>5</sub> layer should be about 200 nm.<sup>4</sup>

HT 800°C: Heat treatment is performed at 800°C for 5 hours at  $3 \times 10^{-6}$  to  $7 \times 10^{-7}$  torr in a vacuum furnace with a base pressure of  $2 \times 10^{-7}$  torr. Nitrogen gas is introduced into the furnace prior to the unloading operation.

HT 800°C/Ti: The niobium sample is placed inside a titanium box and the heat treatment is performed as above.

260°C/5h: The anodized sample is baked at 260°C for 5 hours at a pressure of a few  $\times 10^{-7}$  torr.

EBW: electron beam welding is performed on the niobium sample in the CEBAF EBW machine at a pressure of about  $5 \times 10^{-5}$  torr.

#### **RESULTS AND DISCUSSION**

With a few notable exceptions, all HFS data showed a strong surface peak, representing approximately  $11 \times 10^{15}$  atoms/cm<sup>2</sup> of hydrogen. The depth resolution of the technique makes it impossible to accurately determine the concentration or thickness of this layer, but it is no more than 60 nm thick with a concentration of at least 4 at%.

The surface peak is due at least in part to water uptake and/or hydrocarbon deposition during the experiment, as discussed above. The expected size of this peak was computed based on the dose of analyzing beam and a calibration run on a clean silicon wafer. The surface peak size shown in table 1 is given both raw and (in parentheses) after correction for this effect.

Individual HFS spectra are shown as figures 1 through 12. Sample number 1, which was unprocessed Reactor Grade material, showed much more hydrogen content in its bulk than any of the other samples (between 3.5 and 4.9 at%), even a piece from the same batch that was BCP cleaned removing 90  $\mu$ m of material. An obvious conclusion is that the material contains (after rolling) a damaged, hydrogen rich layer between 0.25  $\mu$ m and 90  $\mu$ m thick.

All of the other non-anodized samples showed between 0.25 and 0.57 at% hydrogen content in the bulk. This is near the detectability limit for HFS, but is clearly a real signal. The anodized samples both showed a clear dip in the top 200 nm zone, indicating that the hydrogen concentration in the oxide is smaller than the metallic niobium.

The differences in "bulk" concentration among the remaining samples is relatively small. The highest readings (0.46 to 0.57 at%) were observed near the surface in the high purity niobium before any chemistry was performed at CEBAF, and in one such sample which received BCP but was not heat treated. The remaining results were all clustered in the 0.25 to 0.37 at% range. This included both CP samples and BCP samples, heat treated and not.

One more anomaly was the additional surface hydrogen content of the EBW sample.

The anticipated reduction in hydrogen content after heat treatment, paralleling improvement in Q-disease reported in other laboratories,<sup>7</sup> was weak at best. Comparisons of sample sets 14, 15 and 16 show a reduction in hydrogen content of 20% to 50%.

Another reported effect is an increase in Q-disease when the temperature of BCP is increased.<sup>7</sup> Samples 14, 23 and 24 seem to support the argument that hydrogen content is increased under these conditions, although again the quantitative changes are small.

A comparison of samples 19 and 18 shows the influence of baking (at 260°C) an anodized sample. There is some evidence that hydrogen diffuses into the bulk.

SIMS gives bulk results at least approximately consistent with HFS, although SIMS is notoriously hard to calibrate. Figure 13 gives hydrogen concentration in the 0.02 at% range for BCP'd high RRR niobium (similar to sample 14). Figure 14 gives hydrogen concentration in the 0.04 at% range for a section of EBW niobium (similar to sample 22).

Our results mostly parallel those of Antoine et al.<sup>10</sup>

## CONCLUSIONS

Hydrogen forward scattering can be used as a probe of hydrogen concentration in niobium. It is adequately sensitive and examines the relevant depth scale for RF properties. More work needs to be done to improve its reliability, however, especially in regards to the interpretation of the surface peak. By itself, it is insufficient to make sense of the surface chemistry. Additional techniques need to be employed. The key piece of information missing at this point is a (diffraction-based) technique that can identify crystallographic phases in the material as a function of temperature.

## REFERENCES

[1] R. W. Roth et al., Proc. 2<sup>nd</sup> European Particle Accelerator Conference, Nice, France (Editions Frontières, Gif-sur-Yvette, 1990), p. 1097

 [2] R. Byrns et al., Proc. 2<sup>nd</sup> European Particle Accelerator Conference, Nice, France, (Editions Frontières, Gif-sur-Yvette, 1990), p. 1073

[3] B. Aune et al., Proc. 1990 Linear Accelerator Conf., Sept. 10-14, 1990, Albuquerque, New Mexico, USA (Los Alamos National Lab, Albuquerque, 1990), p. 253 [4] K. Saito and P. Kneisel, 1991 IEEE Particle Accelerator Conference, San Francisco, California, USA (IEEE, New York, 1991), p. 2387

[5] D. Moffat et al., 1991 IEEE Particle Accelerator Conference, San Francisco, California, USA (IEEE, New York, 1991), p. 2414

[6] G. Enderlein et al., 1991 IEEE Particle Accelerator Conference, San Francisco, California, USA (IEEE, New York, 1991), p. 2432

[7] B. Bonin and R. W. Roth, Proc. 5<sup>th</sup> Workshop on RF Superconductivity (DESY, Hamburg, 1991), p. 210

[8] Charles Evans & Associates, 301 Chesapeake Dr., Redwood City, CA 94063, USA

[9] H. W. Werner and R. P. H. Garten, Rep. Prog. Phys., 1984 47, p. 221

[10] C. Z. Antoine et al., Proc. 5<sup>th</sup> Workshop on RF Superconductivity (DESY, Hamburg, 1991), p. 616

No         rms(µm)         at %         at %         at %           1         Reactor grade-as received         1.09 $7.7$ (4.3)         4.9           2         Reactor grade-BCP (90 µm) $1.24$ $4.4$ (1.0) $0.32$ 13         RRR-as received $0.14$ $4.8$ (1.4) $0.57$ 14         RRR-BCP (90 µm)-HT 800°C/TI $0.58$ $4.4$ (1.0) $0.46$ 15         RRR-BCP (90 µm)-HT 800°C/TI $0.66$ $3.7$ (0.3) $0.27$ 16         RRR-BCP (90 µm)-HT 800°C/TI $0.66$ $4.0$ (0.6) $0.28$ 17         RRR-BCP (90 µm)-HT 800°C/TI $0.66$ $4.0$ (0.6) $0.28$ 17         RRR-BCP (90 µm)-HT 800°C/TI $0.66$ $4.0$ (0.6) $0.28$ 17         RRR-BCP (90 µm)-HT 800°C/TI $0.66$ $4.0$ (0.6) $0.28$ 23         RRR-CP at 23°C (90 µm) $1.03$ $4.0$ (0.6) $0.38$ 24         RRR-CP at 28°C (95 µm) $0.66$ $4.0$ (0.6) $0.36$ 24         RRR-EBW $TABLE II. Hydrogen depth profile of anodized niobium sample         Treatment 0$	Sample	Treatment	Surface	0-500Å	500-1000Å	1000-2500Å	HFS
1       Reactor grade-as received       1.09 $7.7$ (4.3)       4.9         2       Reactor grade-BCP (90 µm)       1.24       4.4 (1.0)       0.32         13       RRR-as received       0.14       4.8 (1.4)       0.57         14       RRR-BCP (90 µm)       0.14       4.8 (1.4)       0.57         15       RRR-BCP (90 µm)       0.58       4.4 (1.0)       0.46         16       RRR-BCP (90 µm)       0.58       3.7 (0.3)       0.25         17       RRR-BCP (90 µm)       0.66       3.7 (0.3)       0.25         17       RRR-BCP (90 µm)       1.03       4.0 (0.6)       0.25         17       RRR-BCP (90 µm)       1.03       4.0 (0.6)       0.26         17       RRR-BCP (90 µm)       1.03       4.0 (0.6)       0.25         18       RRR-BCP (90 µm)       1.03       4.0 (0.6)       0.26         23       RRR-CP at 23°C (90 µm)       1.03       4.0 (0.6)       0.28         24       RRR-CP at 23°C (90 µm)       0.46       5.2 (1.8)       0.36         25       RRR-CP at 23°C (90 µm)       0.46       5.2 (1.8)       0.36         26       RRR-CP at 23°C (90 µm)       0.46       5.2 (1.8)       0.36	No		rms(µm)	at %	at %	at %	Fig.No.
	-	Reactor grade-as received	1.09	7.7 (4.3)	4.9	3.5	-
13       RRH-as received       0.14       4.8       (1.4)       0.57         14       RRH-BCP(90 $\mu$ m)-HT 800°C       0.58       4.4       (1.0)       0.46         15       RRH-BCP(90 $\mu$ m)-HT 800°C/Ti       0.66       3.7       (0.3)       0.27         16       RRH-BCP(90 $\mu$ m)-HT 800°C/Ti       0.66       3.7       (0.3)       0.25         17       RRH-BCP(90 $\mu$ m)-HT 800°C/Ti       0.66       3.7       (0.3)       0.25         17       RRH-BCP(90 $\mu$ m)-HT 800°C/Ti       0.66       3.7       (0.3)       0.25         17       RRH-BCP(90 $\mu$ m)-HT 800°C/Ti-BCP(1mn)       1.03       4.0       (0.6)       0.29         23       RRH-CP at 23°C (90 $\mu$ m)       0.66       4.0       (0.9)       0.33         24       RRH-CP at 28°C (95 $\mu$ m)       0.46       5.2       (1.8)       0.36         25       RRH-CP at 28°C (95 $\mu$ m)       0.46       5.2       (1.8)       0.36         25       RRH-CP at 28°C (95 $\mu$ m)       0.46       5.2       (1.9)       0.36         26       RRH-CP at 28°C (95 $\mu$ m)       0.46       5.2       (1.8)       0.36         25       RRH-CP at 28°C (95 $\mu$ m)       0.46       5.2       0.00	8	Reactor grade-BCP (90 μm)	1.24	4.4 (1.0)	0.32	0.30	2
14       RRR-BCP(90 $\mu m$ )       0.58       4.4 (1.0)       0.46         15       RRR-BCP(90 $\mu m$ )-HT 800°C/Ti       0.83       3.3 (0.0)       0.27         16       RRR-BCP(90 $\mu m$ )-HT 800°C/Ti       0.66       3.7 (0.3)       0.25         17       RRR-BCP(90 $\mu m$ )-HT 800°C/Ti-BCP(1mn)       1.03       4.0 (0.6)       0.25         17       RRR-BCP(90 $\mu m$ )-HT 800°C/Ti-BCP(1mn)       1.03       4.0 (0.6)       0.26         17       RRR-BCP at 23°C (95 $\mu m$ )       0.66       4.0 (0.6)       0.33         24       RRR-CP at 28°C (95 $\mu m$ )       0.66       4.0 (0.6)       0.36         22       RRR-CP at 28°C (95 $\mu m$ )       0.46       5.2 (1.8)       0.36         22       RRR-CP at 28°C (95 $\mu m$ )       0.46       5.2 (1.8)       0.36         22       RRR-CP at 28°C (95 $\mu m$ )       0.46       5.2 (1.8)       0.36         22       RRR-CP at 28°C (95 $\mu m$ )       0.46       5.2 (1.8)       0.36         23       RRR-CP at 28°C (95 $\mu m$ )       0.46       5.2 (1.8)       0.36         24       RRR-CP at 28°C (95 $\mu m$ )       0.46       5.2 (1.8)       0.36         25       RRR-EBW       TABLE II. Hydrogen depth profile of anodized niobium sample       5.3	13	RRR-as received	0.14	4.8 (1.4)	0.57	0.37	n
15       RRR-BCP(90 μm)-HT 800°C/Ti       0.83       3.3       0.0)       0.27         16       RRR-BCP(90 μm)-HT 800°C/Ti-BCP(1mn)       0.66       3.7       0.3)       0.25         17       RRR-BCP(90 μm)-HT 800°C/Ti-BCP(1mn)       1.03       4.0       0.6)       0.29         23       RRR-BCP(90 μm)-HT 800°C/Ti-BCP(1mn)       1.03       4.0       0.6)       0.29         24       RRR-CP at 23°C (90 μm)       0.66       4.0       0.9)       0.33         22       RRR-CP at 28°C (95 μm)       0.46       5.2       0.36       0.36         22       RRR-CP at 28°C (95 μm)       0.46       5.2       0.36       0.33         22       RRR-CP at 28°C (95 μm)       0.46       5.2       0.36       0.36         22       RRR-CP at 28°C (95 μm)       0.46       5.2       0.33       0.36         22       RRR-CP at 28°C (95 μm)       0.46       5.2       0.36       0.36         23       RRR-CP at 28°C (95 μm)       0.46       5.2       0.36       0.36         24       RR-CP at 28°C (95 μm)       0.46       5.2       0.36       0.36         25       RR-CP at 28°C (95 μm)       1.00       0.46       0.36       0.36	14	RRR-BCP(90 µm)	0.58	4.4 (1.0)	0.46	0.33	4
16       RRH-BCP(90 μm)-HT 800°C/Ti       0.66       3.7 (0.3)       0.25         17       RRR-BCP(90 μm)-HT 800°C/Ti-BCP(1mn)       1.03       4.0 (0.6)       0.29         23       RRR-CP at 23°C (90 μm)       0.66       4.0 (0.9)       0.33         24       RRR-CP at 23°C (95 μm)       0.66       4.0 (0.9)       0.36         22       RRR-CP at 28°C (95 μm)       0.46       5.2 (1.8)       0.36         22       RRR-CP at 28°C (95 μm)       0.46       5.2 (1.8)       0.36         22       RRR-CP at 28°C (95 μm)       0.46       5.2 (1.8)       0.36         22       RRR-CP at 28°C (95 μm)       0.46       5.2 (1.8)       0.36         22       RRR-CP at 28°C (95 μm)       0.46       5.2 (1.8)       0.36         23       RRR-CP at 28°C (95 μm)       0.46       5.2 (1.8)       0.36         24       RRR-CP at 28°C (95 μm)       0.46       5.2 (1.8)       0.36         25       RRR-CP at 28°C (95 μm)       0.46       5.2 (1.8)       0.36         25       RRR-CP at 28°C (95 μm)       0.46       5.2 (1.8)       0.36         7       TABLE II. Hydrogen depth profile of anodized niobium sample       0.36       0.33         Sample       Trea	15	RRR-BCP(90 µm)-HT 800°C	0.83	3.3 (0.0)	0.27	0.27	5
17       RRR-BCP(90 μm)-HT 800°C/Ti-BCP(1mn)       1.03       4.0 (0.6)       0.29         23       RRR-CP at 23°C (90 μm)       0.66       4.0 (0.9)       0.33         24       RRR-CP at 28°C (95 μm)       0.46       5.2 (1.8)       0.36         22       RRR-CP at 28°C (95 μm)       0.46       5.2 (1.8)       0.36         22       RRR-EBW       10.0 (6.9)       0.36       0.36         23       RRR-EBW       10.0 (6.9)       0.36       0.36         7ABLE II. Hydrogen depth profile of anodized niobium sample       10.0 (6.9)       0.33         Sample       Treatment       Surface       0-740Å       740-1150Å       1150-2240Å         No       No       ms(μm)       at %       at %       at %       at %	16	RRR-BCP(90 µm)-HT 800 <sup>0</sup> C/Ti	0.66	3.7 (0.3)	0.25	0.25	9
23       RRR-CP at 23°C (90 μm)       0.66       4.0 (0.9)       0.33         24       RRR-CP at 28°C (95 μm)       0.46       5.2 (1.8)       0.36         22       RRR-EBW       0.46       5.2 (1.8)       0.36         23       RRR-EBW       0.46       5.2 (1.9)       0.36         24       RRR-EBW       10.0 (6.9)       0.36         25       RRR-EBW       10.0 (6.9)       0.36         25       TABLE II. Hydrogen depth profile of anodized niobium sample       0.33         Sample       Treatment       Surface       0-740Å       740-1150Å       1150-2240Å         No       No       rms(µm)       at %       at %       at %	17	RRR-BCP(90 µm)-HT 800°C/Ti-BCP(1	mn) 1.03	4.0 (0.6)	0.29	0.25	7
24       RRR-CP at 28°C (95 μm)       0.46       5.2 (1.8)       0.36         22       RRR-EBW       10.0 (6.9)       0.33         22       TABLE II. Hydrogen depth profile of anodized niobium sample         Sample       Treatment       Surface       0-740 Å       740-1150 Å       1150-2240 Å         No       No       at %       at %       at %       at %	<b>53</b>	RRR-CP at 23 <sup>o</sup> C (90 μm)	0.66	4.0 (0.9)	0.33	0.33	8
22RRR-EBW10.0 (6.9)0.33TABLE II. Hydrogen depth profile of anodized niobium sampleSampleTreatmentSurfaceNoTreatmentSurfaceNoat %at %at %	<b>4</b> <b>7</b> 01	RRR-CP at 28 <sup>0</sup> C (95 μm)	0.46	5.2 (1.8)	0.36	0.36	6
TABLE II. Hydrogen depth profile of anodized niobium sample Sample Treatment Surface 0-740Å 740-1150Å 1150-2240Å No at % at % at %	22	RRR-EBW		10.0 (6.9)	0.33	0.33	10
Sample Treatment Surface 0-740Å 740-1150Å 1150-2240Å No at % at % at %		TABLE II. Hydrogen de	pth profile of a	inodized nic	bium sam	ples	
No at % at % at %	Sample	Treatment	rface 0-740Å	740-1150Å	1150-224	0Å >2240Å	HFS
	0 Z		is(μm) at %	al %	81 %	81 %	LIG.N

1 2

0.15 0.30

0.09 0.18

0.40 0.58

4.7 (2.3) 4.4 (2.0)

0.90 0.88

RRR-BCP(90µm)-anodized 100V-

RRR-BCP(90µm)-anodized 100V

19 18 260°C/ 5 hours







Figure 2. Reactor grade - BCP  $(90\mu m)$ 





Par











Figure 12. High RRR - BCP  $(90\mu m)$  - anodized 100V - 260°C/5hours



SRF93I06

